Announcement

5th international conference on thermal & mechanical simulation and experiments in micro-electronics and micro-systems



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May 9 - May 12, 2004

Novotel Tour Noire Brussels, Belgium

EuroSimE 2004 provides7 courses given by professionals90 papers in 18 oral and 3 poster sessionsexhibition and exhibitor presentations

Local organiser: Bart.Vandevelde@imec.be, Marion.Hegemann@imec.be (tel.: +32 16 281 849).



Conference overview

Sunday	May 9, 2004 Short courses
8.30 - 9.00	Registration for short courses (IMEC-Leuven)
9.00 - 12.30	C1: cancelled
	C2: Application of static and dynamic compact thermal models for the thermal analysis of electronic parts (M. Sabry)
	C4: Advanced optimization methods for design and qualification of microelectronics (N. Tzannetakis, G.Q. Zhang)
	C6: Fundamentals of board-level assembly and solder joint reliability (R. Lee)
	C8: Wafer level packaging technologies (E. Beyne)
12.30 - 14.00	Lunch
14.00 - 17.30	C1: cancelled
	C3: Heat sink design and analysis for microelectronic equipment (P. Rodgers, V. Eveloy)
	C5: Lead-free Solder Joints: Reliability Trends and Material Properties (J-P. Clech)
	C7: Microvias and high density interconnects for advanced packaging (R. Lee)
18.00	Bus to Novotel Brussels (conference location)

SIME 200

Monday	May 10, 2004 Conference program, day 1
7.30 - 8.30	Registration
8.30 - 10.40	Session 1: Industrial Trends
10.40 - 11.10	Coffee break
11.10 - 12.40	Session 2: Technology Developments
12.40 - 14.20	Lunch
14.20 - 15.50	Session 3: Virtual Thermal Mechanical Prototyping
14.20 - 15.50	Session 4: Thermal Mechanical Behaviour on Wafer Level
14.20 - 15.50	Session 5: Dynamic Compact Thermal and Electro-Thermal Models
15.50 - 16.30	Coffee break
16.30 - 18.00	Session 6: Experimental and Numerical Interaction
16.30 - 18.00	Session 7: Modelling and Designing of Advanced Packaging
16.30 - 18.00	Session 8: Thermal Behaviour Modelling and Characterization
19.30 - 23.00	Gala dinner in "Roy d'Espagne"

Tuesday	May 11, 2004 Conference program, day 2
8.30 - 10.20	Session 9: Advanced Numerical Simulation Methodologies
8.30 - 10.20	Session 10: Small Scale Thermal and Fluid Aspects in Microsystems
10.20 - 10.40	Coffee break
10.40 - 11.30	Poster session 11, 12, 13.
11.30 - 12.40	Session 14: Modelling of MEMS and Optical Devices
11.30 - 12.40	Session 15: Simulation-Based Thermal Design Strategies
12.40 - 14.10	Lunch
14.20 - 16.10	Session 16: Solder Reliability Behaviour
14.20 - 16.10	Session 17: CFD and FE Modelling of Thermal Performance
16.10 - 16.30	Coffee break
16.30 - 18.00	Special exhibitor session
18.00 - 19.30	Cocktail party

Wednesday	May 12, 2004 Conference program, day 3	
8.30 - 10.00	Session 18: Micro- to Macro-Scale Thermal Design Challenges in Microelectronics	
10.00 - 10.40	Coffee break	
10.40 - 12.30	Session 19: Solder Fatigue	
10.40 - 12.30	Session 20: Characterization and Modelling of Polymer behaviour	
12.30 - 14.00	Lunch	
14.00 - 16.00	Session 21: New Developments in Microelectronics Reliability	
16.00	End of the conference	

Sunday May 9, 2004: Short courses

Place and date : Leuven – (IMEC)

8.30 - 9.00	Registration for short courses (IMEC-Leuven)		
9.00 - 12.30	C2: Application of static and dynamic compact thermal models for the thermal analysis of electronic parts (M. Sabry)		
	C4: Advanced optimisation methods for design and qualification of microelectronics (N. Tzannetakis, G.Q. Zhang)		
	C6: Fundamentals of board-level assembly and solder joint reliability (R. Lee)		
	C8: Wafer level packaging technologies (E. Beyne)		
12.30 - 14.00	Lunch		
14.00 - 17.30	C3: Heat sink design and analysis for microelectronic equipment (P. Rodgers , V. Eveloy)		
	C5: Lead-free Solder Joints: Reliability Trends and Material Properties (J-P. Clech)		
	C7: Microvias and high density interconnects for advanced packaging (R. Lee)		
18.00	Bus to Novotel Brussels (conference location)		

Attention!!! The location of the courses is different from the location of the conference.

Course description:

Course 1:	Cancelled				
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Course 2:	Application of static and dynamic compact thermal models for the thermal analysis of electronic parts		
Instructor	Mohamed-Nabil Sabry, French University, Egypt		
Introduction	The impact of thermal effects on both reliability and performance of electronic systems is no longer to be proved. Static and dynamic thermal effects in electronic circuits manifest themselves at all levels from device to system, with high impact on both reliability and performance of electronic systems, especially as the device feature size shrinks to the nano-scale. Progress in electronic systems has always been marked by a trend for smaller devices and hence larger systems in terms of number of devices. Breaking the barriers at both ends, small and large, is continuously creating new challenges for EDA industry. In fact, for small sizes, the electronic behaviour will be more affected by other physical phenomena such as thermal, electromagnetic and mechanical including quantum effects. This constitutes the first challenge. On the other hand, miniaturization enables us to construct systems containing millions, or perhaps billions, of different elements. Hence, modelling, simulating and moreover optimising these systems, is another challenge. It is evident that analysing a thermal problem in its full details, involving fluid dynamics, heat transfer by all modes (conduction, convection and radiation) including non-linear effects together with all the electronic details of the system is simply a fiction. Yet, electronic and thermal problems interfere at all levels, and we need to predict system performance and reliability before fabrication. Hence, new design methodologies have to be adopted based on top - down design approach. This is a "divide and conquer" approach, heavily relying on hierarchical sets of compact models at different levels of abstraction.		
	to the dynamic case. The wealth of knowledge accumulated has largely deserved a structured presentation in order to correctly grasp underlying physics as well as adequate methodologies to handle different problems according to their inherent nature as well as design needs and constraints.		
Objectives	The course aims at giving attendees a rational and structured understanding of the nature of both compact models as well as physical problems they are intended to address, whether in static or dynamic regimes, in order to adequately build and use these compact models for the design and analysis of electro-thermal problems arising in electronic systems.		

Course Outline	 Introduction When and why should we care about electro-thermal effects Why should we use compact models Place of compact models in simulation and design flow Properties of a compact model General forms for static and dynamic models Constraints that must be satisfied by compact models, validity checks Precision of a compact model When should we use a dynamic compact model? Slow dynamics Fast dynamics Fast dynamics Structural assembly approach Integral approach The structure function Modal approach Special problems Nonlinear problems, Radiation Convection 	
Who should attend?	The course addresses the needs of engineers, scientists as well as technical strategic decision makers, involved in thermal management of electronic systems. Although the course presents most recent advances in the field of static and dynamic compact models with sufficient details to let this knowledge be operational in concrete applications, it does not assume prior knowledge of these issues and hence is of interest for both experts and new actors in this area	
About the instructor	Prof. Mohamed-Nabil Sabry is the dean of engineering faculty in the French University in Egypt. He holds a Doctorat es Sciences Degree from the National Polytechnic Institute in Grenoble, France 1984, about modeling and simulation of 3D convective problems and has been involved since then in thermal and electro-thermal issues at different levels both in academic and industrial context. He was formerly with Mentor Graphics where he was the engineering manager of analog simulation activities worldwide, as well as the French Nuclear Research Center. He also worked with different universities in France (INP-Grenoble) and in Egypt (Mansoura U., American U. and finally the French U.). For his publications on compact models, he was awarded the Harvey Rosten award of excellence in 2002. He is also member of the program committee of THERMINIC, a panel member in many international conferences (THERMINIC, VLSI Test Symposium) and a reviewer in many international scientific journals dealing with this subject (IEEE/CPT, IEEE/Electron Device letters, Microelectronics Journal, ASME/Journal of Electronic Packaging). His published works cover the whole spectrum of electro-thermal analysis from transistor level to system level.	

Course 3:	Heat sink design and analysis for microelectronic equipment	
Instructor	Peter Rodgers, CALCE Electronic Products and Systems Center, University of Maryland, USA Valérie Eveloy, Electronics Thermal Management Ltd., Ireland	
Introduction	Heat sinks are the most common, cost-effective hardware employed for the thermal management of microelectronic equipment, with applications spanning from microchannel cooling to component- and circuit board thermal control. Heat sinks function by extending the surface area of heat dissipating surfaces through the use of fins. Their design and analysis is one of the most extensive research areas in electronics cooling. Ever-rising electronic component power dissipation, combined with both the demand for more compact and lighter equipment, and manufacturing constraints, place increasing challenges on the optimisation of heat sink thermal performance today. This is compounded by shortening product design cycle times, which heighten the requirement for innovative thermal design methods enabling accurate heat sink designs to be generated and quickly assessed. An efficient thermal design process involves the use of analytical and semi-empirical calculations to establish an initial heat sink design, which is refined by numerical analysis to account for the impact of the application environment on thermal performance. The effectiveness of the heat sink design ultimately needs to be verified by experimentation. The course provides an overview of the state-of-the-art and general trends in heat sink design. Apart from convective and radiative heat transfer optimisation, the course addresses key issues in advancing heat sink thermal performance, including contact thermal resistance, integration of heat spreading technologies and entropy minimisation. Practical case studies dealing with heat sink design optimisation are presented.	
Objectives	This course provides a comprehensive treatment of the design and analysis of heat sinks. It combines theoretical and practical information to successfully design or select cost-effective heat sinks for microelectronic equipment. The attendee will gain an appreciation of both the fundamental performance limits of heat sinks, and current state-of-the-art in heat sink technology.	

Course Outline	 Introduction Fundamentals of heat transfer: conductive, convective and radiative heat transfer processes Thermal analysis and design process: Application of analytical, experimental and numerical analyses, overview of the latest commercial thermal design software packages Heat dissipation trends in electronic systems: heat transfer chain, limits of air-cooling: passive versus active Evolution of Heat Sink Design and Analysis Analytical analysis: Fin efficiency, Radiative heat transfer models Experimentation: derivation of correlations for the convective heat transfer coefficient as a function of heat sink geometry and convective environment; friction factor correlations Numerical analysis: Investigation of thermofluid phenomena: Use of Computational Fluid Dynamics (CFD) methods to predict heat sink performance in application environment Heat sink design optimisation
Comme	
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	Environmental and physical conditions; Initial feasibility study
	Heat sink optimisation: Convective and radiative performance; Conductive performance (Fin efficiency, heat spreading: heat pipes, vapour chambers, improved thermal conductivity
	materials), design for manufacturability, least-energy optimisation
	5. Current Design and Analysis Methods for Air-Cooled Heat Sinks (Cont'd)
	• Heat sink attachment: contact thermal resistance and interface materials, properties of interface materials;
	Types of interface materials
	Airflow management For particular
	Fan performance Fan/blower/impeller selection; Assessment of vendor specified fan curve performance
	Change in fan curve characteristics due to application environment
	Effect of grille and filter open area on system impedance
	Compact modelling of heat sink thermofluid characteristics for system-level numerical analysis
	6. Case studies: heat sink design and application
	Microprocessor cooling Take any maintain a biast wait as a line
	Telecommunication cabinet unit cooling Summary
Who should	The course will benefit engineers, managers and scientists involved in the thermal management or reliability of electronic systems. It is aimed at participants with varying expertise levels in thermal management, from novice to
attend?	advanced.

About the instructor	 Dr. Peter Rodgers is an Assistant Research Professor at the University of Maryland, College Park, where he supports the thermofluid research of the CALCE Electronic Products and Systems Center. He holds a Ph.D. degree in mechanical engineering from the University of Limerick, Ireland and has extensive experience of electronic equipment thermal design and characterisation. He was formerly with Electronics Thermal Management Ltd., Ireland, and the Nokia Research Center, Finland, where he consulted on electronics cooling. He is recipient of the 1999 Harvey Rosten Award for Excellence, awarded for his publications on the application of CFD analysis to electronics thermal design. Other research interests include the design of high-performance heat sinks, and the development of advanced experimental techniques to characterise thermofluid phenomena in electronic systems. He is a participant in the JSME Project, "Design and Manufacture of High-Performance Heat Sinks for Microelectronic Equipment". He is a member of several international conference program committees and has authored or co-authored approximately forty conference and journal publications on a broad range of topics related to electronics cooling. He has been an invited lecturer, track- and session chair and panelist at international conferences. Dr. Valérie Eveloy is with Electronics Thermal Management Ltd., a research and consulting firm specialized in electronics cooling. She has been involved in electronics cooling for nine years, and was previously a Research Engineer with the Nokia Research Center, Finland, where her activities focused on the thermal management of telecommunication products and the selection of RF IC packaging solutions. She has authored or co-authored over twenty five conference and journal publications, holds an M.Sc. degree in physical engineering from the National Institute of Applied Science (INSA), France, and a Ph.D. degree in mechanical engineering from Dublin City University, Ireland.
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Course 4:	Advanced optimisation methods for design and qualification of microelectronics	
Instructor	Nick Tzannetakis, NOESIS, Belgium Kouchi Zhang, Philips, The Netherlands	
Background & relevancy	The rapid technological development trends of microelectronics and microsystems are mainly characterized by miniaturization down to nano-scale, increasing levels of technology/function integration and eco-design, while the business trends are mainly characterized by cost reduction, shorter time-to-market and outsourcing. These trends lead to increased chances and consequences of failures, increased design complexity, decreased product development and qualification times, dramatically decreased design margins and increased difficulties to meet quality, robustness and reliability requirements. To achieve competitive product/process development and manufacturing excellence, it is vital to know and to apply the advanced optimization methods for design and qualification of microelectronics.	
Course Outline	 Development trends of Microelectronics and Microsystems The state-of-the-art of design and qualification of microelectronics Basic theories of advanced optimization methods and tools Exposure to Process Integration Techniques supporting the application of the advanced optimization on industrial problems Case studies including software demonstrations Challenges and future development and perspectives 	
What You Will Learn	This half-day course provides the participants with a unique chance to learn both the overview on the state-of-the-art methodologies, and the detailed ways of working & applications via both basic theory and case studies. The added business values will also be demonstrated.	
Who should attend?	Microelectronics design engineers, reliability engineers, product/process developers and managers, thermal and mechanical analysts, researchers, graduates, PhD students and postdoc.	
About the instructor	Nikolas Tzannetakis (1960) acquired an MSc. degree in Mechanical Engineering (1985) and an MSc. In Aerospace Engineering (1991) from the University of Michigan (USA). From 1985 to 1990 he worked in various positions in the area of structural analysis and optimization. From 1990 to 1996 he worked exclusively in the area of application of design optimization methods to industrial design applications. From 1996 to 1999 he served as the Product Manager of LMS OPTIMUS, at LMS International, working in the development, promotion and management of the software package. From 1999 until 2003 he managed the development of LMS Virtual.Lab Integrated Simulation software package. He is now the Chief Technical Officer of NOESIS Solutions a company focusing in the area of Process Integration and Design Optimization. He has published over 20 papers in the area of Process Integration and Design. Beside his responsibilities in Technical University of Eindhoven, Prof. Dr. G.Q. Zhang is a principal scientist and technology domain leader at Philips (CFT) Centre For Industrial Technology, The Netherlands. Prof. Zhang is author and co-author for more than 100 scientific publications, including journal and conference papers, book and invited keynote lectures. His scientific interests include virtual prototyping and virtual qualification, development of fundamental and application knowledge of computational & experimental mechanics, advanced optimization methods and reliability engineering, and especially their applications in microelectronics, Microsystems and nanotechnology.	

Course 5:	Lead-free Solder Joints: Reliability Trends and Material Properties
Instructor	Jean-Paul Clech, EPSI Inc., USA
Course Outline	 Material properties (incl. physical properties, creep data in tension and shear): Sn-Ag, Sn-Ag-Cu. Creep deformations and creep rupture: temperature-dependent activation energy, effect of alloy composition on mechanical properties. Fatigue curves, failure modes. Thermal cycling reliability data: 100% lead-free data (Sn-Ag-Cu), mixed assemblies (SnPb balls + lead-free paste; SAC balls + HASL); data for leadless components (LCCC, discretes), leaded packages, BGA (PBGA, CCGA, CBGA), CSPs, Flip-Chip with & without underfill. Impact of components and test conditions on the relative reliability of lead-free versus SnPb assemblies. Effect of component and board finish on lead-free solder joint life (thermal cycling & drop test). On-going developments: acceleration factors, constitutive modeling, life prediction models.
What You Will Learn	Solder joint reliability issues, which are well understood for SnPb assemblies, have been compounded by the introduction of lead-free and mixed (lead-free + SnPb) assemblies, limited field experience with lead-free solders, and ever more demanding end-use reliability requirements. The thermo-mechanical properties of Sn-Ag-Cu based alloys are also quite different from those of conventional SnPb. It is thus critical to understand what factors affect both the properties and the long term reliability of lead-free solders. This workshop provides an analysis and synthesis of the latest reliability information for popular lead-free alloys such as Sn-Ag-Cu (SAC). The performance of lead-free assemblies is put in perspective with that of SnPb assemblies. Material properties and fatigue curves are presented in an attempt to explain differences in the reliability of, and in the acceleration factors for SnPb and lead-free assemblies. The significance and the effect of alloy composition on thermo-mechanical properties is also discussed. Accelerated test results are presented for common components assembled onto circuit-boards using lead-free solder: leadless ceramic chip carriers, resistors, leaded packages, CBGA, CCGA, PBGA, flip-chip (with and without underfill), chip scale and wafer scale packages. Reliability risks are quantified for mixed assembly circuit-boards (lead-free + SnPb). Effects of common board (HASL, Ni/Au, OSP) and component finish are also discussed. The surveyed data indicates a strong dependence of lead-free solder joint reliability on component type, CTE mismatch as well as test conditions. In addition to the workshop slides, the hand-outs include an extensive list of references on lead-free solder mechanical properties and joint reliability.
Who should attend?	Circuit board designers, packaging engineers, design, manufacturing, quality or reliability professionals and managers who are responsible for, or plan to implement lead-free assembly technologies in their companies' products. Engineers and scientists involved in solder alloy development and characterization.
About the instructor	Jean-Paul Clech has over 18 years of practical experience in SMT quality and reliability assurance. He maintains one of the largest databases of solder joint reliability failures in the industry and is constantly challenged by problems brought about by new and emerging technologies. His current research interests are in BGA, CSP, flip-chip and lead-free assembly reliability. Jean-Paul is the founder of EPSI Inc. in Montclair, NJ. His responsibilities include technical consultation and problem solving for clients across the electronics industry and the development of engineering tools and training programs to prevent or solve reliability problems in electronics packaging and assembly. He is the principal developer of the "Solder Reliability Solutions" model and application software. He previously was Manager of Electronic Packaging at a European super-computer start-up, a Member of the Technical Staff and then consultant at AT&T Bell Labs. Jean-Paul received the Diplôme d' Ingénieur from Ecole Centrale de Paris, France (Materials Science major), and the M.S. and Ph.D. degrees in Mechanical Engineering from Northwestern University, Evanston, IL. His technical interests include thermal, mechanical, structural and fatigue behavior of electronic materials, packages and assemblies, and the application of engineering principles to the physical design and manufacturing of electronic systems. He is the author of over thirty-five technical papers, a frequent speaker at technical conferences, and has been an invited lecturer and workshop instructor at universities and corporations in Asia, Europe and North America. He is an active member of ASME, IEEE, IMAPS, TMS and SMTA.

Course 6:	Fundamentals of board-level assembly and solder joint reliability
Instructor	Ricky Lee, Hong Kong University of Science and Technology, Hong Kong
Outline	Introduction to soldering and surface mount technology (SMT); materials and processes for solder bumping; solder ball shear strength tests and analyses; printed circuit board (PCB) assemblies; destructive and non-destructive inspection methods; board level reliability under thermo-mechanical loading; accelerated temperature cycling tests; mechanical drop tests; computational and experimental mechanics for solder joint reliability; lead-free solder issues; design for reliability and environment.
Description	One of the major tasks of microelectronic packaging is to provide the ICs and components with passages for I/O signals, power, and ground. The interconnections between the chip and the substrate, and between the package and the printed circuit board are very critical to the electronics manufacturing industries. This workshop is aimed at providing comprehensive information on the most significant development and latest technologies for SMT solder joint interconnections in microelectronic packaging. During the course of this workshop, the topics listed in the outline will be discussed in great details. Emphases will be placed on the materials, processes, inspection, testing, analysis, and reliability issues. From this workshop, the attendees will acquire a profound understanding in the most significant issues for board level assemblies and solder joint reliability.
About the instructor	Ricky Lee received his Ph.D. degree from Purdue University in 1992. Currently, he is Associate Professor of Mechanical Engineering and Director of EPACK Lab at HKUST. He also sits on the Editorial Advisory Board of two international journals and is serving as Associate Editor for IEEE Transactions on Components & Packaging Technologies and IEEE Transactions on Advanced Packaging. Ricky is an ASME Fellow and a senior member of IEEE. He was Vice-Chair of Hong Kong Section, ASME International (1997 & 1998) and Chair of Hong Kong Chapter, IEEE-CPMT Society (2001 & 2002). Currently he is an Executive Committee Member of ASME-EPPD and a member of Board of Governors, IEEE-CPMT. Ricky has served as Track Organizer and Session Chair for many international conferences and he is a member of Program Committee (Interconnections) of ECTC. Besides, he has been invited to deliver short courses and seminars around the world (including ECTC, NEPCON-West and SEMICON-Singapore/Taiwan). Ricky has published numerous technical papers in international journals and conference proceedings, and is the co-author of three books- Chip Scale Packages (CSP): Design, Materials, Process, Reliability, and Applications; Microvias for Low-Cost High Density Interconnects; and Electronics Manufacturing with Lead-Free, Halogen-Free, and Conductive-Adhesive Materials. Furthermore, he is the two-time recipient (2000 & 2001) of JEP Best Paper Award, ASME Transactions: Journal of Electronic Packaging.

Course 7:	Microvias and high density interconnects for advanced packaging		
Instructor	Ricky Lee, Hong Kong University of Science and Technology, Hong Kong		
Objectives	This course will introduce the cutting-edge information on the most important development and latest research results in applying microvias and high density interconnect technologies to advanced packaging. For professionals active in microelectronic packaging research and development, those who wish to master high density interconnect technologies, and those who need to choose a cost effective design and highyield manufacturing process for their electronic systems, this is a timely summary of progress in all aspects of this fascinating field. The lecture contents are based on the instructor's books on electronic packaging, his recent research results, and interactions with the packaging and assembly industries. The scope of course covers flip chip and CSP technologies. With the information provided in this lecture, the attendees will acquire a practical understanding in the design, materials, processes, analysis, and reliability issues of high-density interconnection technologies.		
Course Outline			
Who should attend?	This short course is intended for research scientists, professional engineers and technical managers who are involved in IC packaging, component assembly, materials and processing, contract manufacturing and marketing		

	Ricky Lee received his Ph.D. degree from Purdue University in 1992. Currently, he is Associate Professor of
	Mechanical Engineering and Director of EPACK Lab at HKUST. He also sits on the Editorial Advisory Board of two
	international journals and is serving as Associate Editor for IEEE Transactions on Components & Packaging
	Technologies and IEEE Transactions on Advanced Packaging. Ricky is an ASME Fellow and a senior member of
	IEEE. He was Vice-Chair of Hong Kong Section, ASME International (1997 & 1998) and Chair of Hong Kong
	Chapter, IEEE-CPMT Society (2001 & 2002). Currently he is an Executive Committee Member of ASME-EPPD and
About the	a member of Board of Governors, IEEE-CPMT. Ricky has served as Track Organizer and Session Chair for many
instructor	international conferences and he is a member of Program Committee (Interconnections) of ECTC. Besides, he has
	been invited to deliver short courses and seminars around the world (including ECTC, NEPCON-West and
	SEMICON-Singapore/Taiwan). Ricky has published numerous technical papers in international journals and
	conference proceedings, and is the co-author of three books- Chip Scale Packages (CSP): Design, Materials, Process,
	Reliability, and Applications; Microvias for Low-Cost High Density Interconnects; and Electronics Manufacturing
	with Lead-Free, Halogen-Free, and Conductive-Adhesive Materials. Furthermore, he is the two-time recipient (2000 &
	2001) of JEP Best Paper Award, ASME Transactions: Journal of Electronic Packaging.

Course 8:	Wafer level packaging technologies			
Instructor	Eric Beyne, IMEC, Belgium			
Course Outline	 Introduction Introduction Impact of the IC-roadmaps on interconnection and packaging technologies Traditional packaging approaches System-in-a-package technology Wafer-level packaging (WLP) techniques - definitions Wafer level packaging technologies Flip chip technology Wafer level redistribution technologies Chip-sized package technologies with overview of different industrial appoaches Electrical considerations in WLP Electrcial parasitics package level interconnects Thermo-mechanical considerations Impact on reliability solder joints Impact on reliability redistribution metallisation Technology & FEM co-design for improved reliability Thermal considerations Economic aspects Summary 			

Monday May 10, 2004: *Technical programme day 1*

 7.30
 60
 Registration

 8.30
 Start Monday Morning Sessions

		Opening Session	
8.30	10	Opening	
Sessior	n 1:	Keynote session: Industrial Trends	
8.40	30	Keynote: Roadmap Challenges – There is More than Moore	
		A. J. van Roosmalen	
		Philips Semiconductors, Eindhoven, the Netherlands	
9.10 30 Keynote: Opportunities and Challenges for Telecommunications Technology		Keynote: Opportunities and Challenges for Telecommunications Technology	
		J. Rantala	
		Nokia Research Center, Helsinki, Finland	
9.40	30	Keynote: Trends in automotive electronics	
		H. Casier	
		AMI Semiconductor Belgium BVBA, Oudenaarde, Belgium	
10.10	0 30 Keynote: Trends & Challenges in Microsystems Packaging		
		M. K. Iyer	
		Microsystems, Modules & Components Lab, Institute of Microelectronics (IME), Singapore	

10.40 30 Break

Session	ı 2:	Keynote session: Technology Developments	
11.10	30	Keynote: Nano-electronics in Biological Applications	
		G. Borghs	
		IMEC, Leuven, Belgium	
11.40	30	Keynote: Reliability Challenges and Recent Advances for Cu Interconnects	
		Paul S. Ho ^{a*} , Ki-Don Lee ^b , Sean Yoon ^a , Guotao Wang ^a	
		^a Laboratory for Interconnect and Packaging, University of Texas at Austin, USA	
		^b Silicon Technology Development, Texas Instruments, Inc., Dallas, USA	
12.10	30	Keynote: From Macro-Cooling to Micro-Reliability	
		M.R.D. Davies	
		Stokes Research Institute, University of Limerick, Ireland	

12.40 100 Lunch

14.20 Monday Afternoon Sessions

				Parallel sessions	
14.20-1	15.50	Session 3		Session 4	Session 5
		Virtual Thermal Mechanical Prototyping		Thermal Mechanical Behavior on Wafer Level	Dynamic Compact Thermal and Electro-Thermal Models
Session	n 3:	Virtual Thermal Mechanical Pr	rot	otyping	
14.20				ages an Driel, H.J.L. Bressers ³	
14.50	20	Thermo-Mechanical Stress Modelling of MOS Device with Electro- thermal Considerations P. Tounsi [*] , J.P. Fradin ^{***} , X. Chauffleur ^{***} , Ph. Dupuy ^{**} , J.M. Dorkel [*] , A. Marty [*] , A. Deram ^{**} ^{*)} LAAS/CNRS, Toulouse Cedex, France ^{***} MOTOROLA Semiconducteurs SA, Toulouse Cedex, France ^{***†} EPSILON Ingénierie, California, Labège Cedex, France			
15.10	20	FEM-based Method to Determinate Mechanical Stress Evolution during Process Flow in Microelectronics – Application to Stress-Voiding S. Orain ¹ , J.C Barbé ² , X. Federspiel ¹ , P. Legallo ³ , H. Jaouen ⁴ ¹⁾ PHILIPS semiconductors, Crolles cedex ; France ²⁾ CEA-DRT-LETI/DTS, Grenoble Cedex, France ³⁾ CEA-DRT/DTEN, Grenoble Cedex, France ⁴⁾ STMicroelectronics, Crolles Cedex, France			
15.30	20	On Wire Failures in M W.D. van Driel¹ , J.H.J. J ¹⁾ ATO Innovation/Philips ²⁾ Center for Industrial Te	Mi Ian s So ech	cro-electronic Packages sen, G.Q. Zhang ² ,M.A.J. van Gils ² , emiconductors, Nijmegen, The Nethe nology/Philips, Eindhoven, The Neth ology, 2628 CD Delft, The Netherland	rlands herlands

Session	ession 4: Thermal Mechanical Behavior on Wafer Level		
14.20	30	Keynote: A Finite Element Study of Process Induced Stress in the Transistor Channel: Effects of	
		Silicide Contact and Gate Stack	
		C.Torregiani ^{1,2} , J. Liu ³ , B.Vandevelde ¹ , D.Degryse ¹ , M.J.Van Dal ⁴ , A. Benedetti, A.Lauwers ¹ ,	
		K.Maex ^{1,2} .	
		¹⁾ IMEC, Leuven, Belgium; ²⁾ E.E. Dept. K.U.Leuven, Leuven, Belgium	
		³⁾ E.E. Dept. Stanford University, Stanford, California, USA	
		⁴⁾ Philips Research Leuven, Leuven, Belgium	
14.50	20	Effect of Metal Layout Design on Passivation Crack Occurrence using both	
		Experimental and Simulation Techniques	
		R.B.R van Silfhout ¹ , W.D. van Driel ² , Y.Li ² , M.A.J. van Gils ¹ , J.H.J. Janssen ² , G.Q. Zhang ¹ , G.	
		Tao^2 , J. Bisschop ² , L.J. Ernst ³	
		¹⁾ Philips Centre for Industrial Technology, Eindhoven, The Netherlands	
		²⁾ Philips Semiconductors, ATO Innovation, Nijmegen, The Netherlands	
		³⁾ Delft University of Technology, The Netherlands	
15.10	20	Probability of Silicon Fracture in Molded Packages	
		C. Bohm*, T. Hauck*, W. H. Müller**, A. Juritza	
		*) Motorola GmbH, Schatzbogen 7, 81829 München	
		**) Technische Universität Berlin, Einsteinufer 5, 10587 Berlin	
15.30	20	Interfacial Sliding and Plasticity in Back-end Interconnect Structures of Microelectronic	
		devices	
		I. Dutta ¹ , D. Pan, C. Park ¹ , J. Vella ²	
		¹⁾ Center for Materials Science and Engineering, Department of Mechanical	
		Engineering, Naval Postgraduate School, Monterey, CA, USA	
		²⁾ Process and Materials Characterization Laboratory, Motorola, Tempe, AZ, USA	

Session 5: Dynamic Compact Thermal and Electro-Thermal Models					
14.20	30	Keynote: Empirical Validation of Thermal Dynamics in a Silicon Microthruster: Influence of the			
		Boundary Conditions			
		M. Salleras, I. García, J. Palacín, M. Puig, J. Samitier, S. Marco			
		Sistemes d'Instrumentació i Communicacions, Departament d'Electrònica, Universitat de Barcelona, Spain			
14.50 20 Compact Electro-thermal Models of Semiconductor Devices with Multiple Heat Sou					
		C. Bohm, T. Hauck, E.B. Rudnyi, J. G. Korvink			
		Motorola, Germany IMTEK, University of Freiburg, Germany			
15.10 20 Electro-Thermal Transistor Models in the SISSI Electro-Thermal IC Simulato		Electro-Thermal Transistor Models in the SISSI Electro-Thermal IC Simulator			
		V.Székely, A.Poppe, G.Hajas			
		Budapest University of Technology and Economics, Hungary			

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15.50 40 Break
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	Parallel sessions		
16.30-18.00	Session 6	Session 7	Session 8
	Experimental and	Modeling and Designing	Thermal Behavior Modeling and
	Numerical Interaction	of Advanced Packaging	Characterization

Session	n 6:	Experimental and Numerical Interaction
16.30	30	Keynote: Computational Model Validation with Experimental Data from Temperature Cycling Tests of PBGA Assemblies for the Analysis of Board Level Solder Joint Reliability R. Lee, D. Lau Electronic Packaging Laboratory, Department of Mechanical Engineering Hong Kong University of Science & Technology, Hong Kong
17.00	20	PWB Warpage Analysis and Verification using an AP210 Standards-based Engineering Framework and Shadow Moiré D. Zwemer ¹ , S. McCarron ¹ , A. Spradling ¹ , R. Peak ² , M. Bajaj ² , T. Thurman ³ , M. Dickerson ⁴ , L. Klein ⁵ , G. Liutkis ⁵ , K. Brady ⁶ , J. Messina ⁶ ¹⁾ AkroMetrix LLC, USA ²⁾ Georgia Institute of Technology, USA ³⁾ Rockwell Collins, USA ⁴⁾ InterCAX LLC, USA ⁵⁾ LKSoft, USA ⁶⁾ NIST, USA
17.20	20	Novel Numerical and Experimental Analysis of Dynamic Responses under Board Level Drop Test Tong Yan Tee ^a , Jing-en Luan ^a , Eric Pek ^b , Chwee Teck Lim ^b , Zhaowei Zhong ^c ^a STMicroelectronics, Singapore ^b National University of Singapore, ME Dept, Singapore. ^c Nanyang Technological University, School of MPE, Singapore.
17.40	20	Finite Element Modelling of Crack Detection Tests <i>S Ridout</i> ¹ , <i>M Dusek</i> ² , <i>C Bailey</i> ¹ , <i>C Hunt</i> ² ¹⁾ Centre for Numerical Modelling and Process Analysis, University of Greenwich, Greenwich, UK ²⁾ NPL Materials Centre, National Physical Laboratory,, Teddington, UK

Session 7:		Modeling and Designing of Advanced Packaging
16.30	30	Keynote: Design, Fabrication and Comparison of Lead-Free/Eutectic Solder Joint Reliability of
		FlipChip Package
		Chih-Tang Peng, Kuo-Ning Chiang, Terry Ku, Kenny Chang
		National Tsing Hua University, Taiwan
17.00	20	Virtual Qualification of Moisture Induced Failures of Advanced Packages
		M.A.J. van Gils ¹ , W.D. van Driel ² , G.Q. Zhang ³ , H.J.L. Bressers ² ,
		R.B.R. van Silfhout ¹ , X.J. Fan ⁴ , J.H.J. Janssen ²
		¹⁾ Philips Center for Industrial Technology, Eindhoven, The Netherlands
		²⁾ ATO Innovation/Philips Semiconductors, Nijmegen, The Netherlands
		³⁾ Technical University of Eindhoven, Eindhoven, The Netherlands
		⁴⁾ Philips Research-USA, Briarcliff Manor, New York, USA
17.20	20	Finite Element Analysis of an Improved Wafer Level Package using Silicone Under
		Bump (SUB) Layers
		M. Gonzalez ¹ , M. Vanden Bulcke ¹ , B. Vandevelde ¹ , E. Beyne ¹ ,
		Y. Lee ² , B. Harkness ² , H. Meynen ²
		¹ IMEC, Leuven, Belgium
		² Dow Corning Corporation
17.40	20	Crack and Delamination Risk Evaluation of Thin Silicon Applications based on Fracture
		Mechanics Approaches
		J. Auersperg ^{1,7} , D. Vogel ¹ , B. Michel ¹
		¹⁾ Fraunhofer Institute for Reliability and Microintegration Berlin (IZM),
		Dept. Mechanical Reliability and Micro Materials, Berlin, Germany
		²⁾ AMIC Angewandte Micro-Messtechnik GmbH, Berlin, Germany

Session	n 8:	Thermal Behavior Modeling and Characterization
16.30	30	Keynote: Numerical Simulation and Experimental Verification of the Thermal Contact Properties
		of the Polymers Bonds
		T. Fałat, A. Wymysłowski, K. Friedel, J.Felba
		Wrocław University of Technology, Poland
17.00	20	Experiments on Behaviour of Power Silicon PN Junctions under Reverse Bias Voltage at High
		Temperature
		V.V.N. Obreja ¹ , C. Codreanu ¹ , K. Nuttall ² , O. Buiu ²
		¹⁾ National R&D Institute for Microtechnology, Romania
		²⁾ Liverpool University, UK
17.20	20	Parameter Calibration on Post-ion-implantation Dopant Diffusions
		J. Fu, W.Crans ² , W.J. Eijsenga ²
		¹⁾ X-FAB Semiconductor Foundries, Erfurt, Germany
		²⁾ TU Delft, ITS-Faculty/DIMES, Electronic Components, Technology and Materials (ECTM)-Lab, Delft,
		The Netherlands

18.00 End of 1st day Technical Sessions

19.30

Gala dinner in Roy d'Espagne (Great Market place in heart of Brussels)









TuesdayMay 11, 2004:Technical programme day 2

8.30 Start Tuesday Morning Sessions

 Parallel sessions

 8.30-10.20
 Session 9
 Session 10

 Advanced Numerical Simulation Methodologies
 Small Scale Thermal and Fluid Aspects in Microsystems

Session 9:		Advanced Numerical Simulation Methodologies
8.30	30	Keynote: Automated FEM Mesh Optimization for Nonlinear Problems Based on Error Estimation
		S. Rzepka
		Infineon Technologies SC 300 Dresden, MDC RM, Dresden, Germany
9.00	20	Advanced Numerical Prototyping Methods in Modern Engineering Applications
		W.D. van Driel ¹ , J. van de Peer ³ , N. Tzannetakis ³ , A. Wymysłowski ⁴ , G.Q. Zhang ²
		¹⁾ ATO Innovation/Philips Semiconductors, Nijmegen, The Netherlands
		²⁾ Center for Industrial Technology/Philips, Eindhoven, The Netherlands
		³⁾ Noesis, Leuven, Belgium
		⁴⁾ Wroclaw University of Technology, Wroclaw, Poland
9.20	20	Reliability-Based Design Optimization for Land Grid Array Solder Joints Under
		Thermo-Mechanical Load
		Zhenxue Han ¹ , Bo Wang ¹ , Leon Xu ² , Tommi Reinikainen ² , Ren Wei ²
		¹⁾ University of Texas at Arlington, USA
		²⁾ Nokia, USA
9.40	20	Finite Element Analysis of Ultra Thin BGA Package: First and Second Level Reliability
		P. Limaye ¹ , B. Vandevelde ¹ , H. deVries ² , D. Degryse ¹ , K. Slob ² , C. van Veen ² , R. Labie ¹
		¹⁾ IMEC, Leuven, Belgium
		²⁾ Philips CFT (Eindhoven), The Netherlands
10.00	20	Application of Simulation-based Decision Making in Product Development of an RF
		Module
		M. Lindgren ^{1,2} , I. Belov ² , M. Törnvall ¹ , P. Leisner ^{2,3} ,
		¹⁾ Kitron Development AB, Jönköping, Sweden
		²⁾ School of Engineering, Jönköping university, Sweden
		³⁾ Acreo AB, Jönköping, Sweden

Session 10:		Small Scale Thermal and Fluid Aspects in Microsystems
8.30	30	Keynote: Data on the Velocity Slip and Temperature Jump Coefficients
		F. Sharipov
		Universidade Federal do Paran´a, Brazil
9.00	20	Shear Driven Micro-Flows of Gaseous Mixtures
		D. Valougeorgis, S. Naris
		University of Thessaly, Greece
9.20	20	Effect of Slip on Transient Liquid Flow Development in Micro-Channels
		M.N. Sabry ¹ , A.R. Abdel-Rahim ² , M.H. Mansour ²
		¹) Université Française d'Egypte, Egypt
		²) Mansoura University, Egypt
9.40	20	Model Order Reduction of 3D Electro-Thermal Model for a Novel Micromachined
		Hotplate Gas Sensor
		T. Bechtold ¹ , J. Hildenbrand ¹ , J. G. Korvink ¹ , J. Wollenstein ²
		¹⁾ IMTEK, University of Freiburg, Germany
		²⁾ Institute for Physical Measurement Techniques, Germany
10.00	20	Non-contact Thermal Conductivity Measurements of P-doped and N-doped Gold
		Covered Natural and Isotopically-Pure Silicon and their Oxides
		M. G. Burzo, P. L. Komarov, P. E. Raad
		Southern Methodist University, Dallas
		· · ·

10.20 20 Break

	Parallel poster sessions			
10.40-11.30	Session 11	Session 12	Session 13	
	Modeling in Micro	Designing for	Material Characteriza	tion and
	Technology	Reliability	Modeling	

Session	n 11:	Poster session: Modeling in Micro Technology
10.40	50	Design and analysis of novel glass WLCSP structure
		Chang-Ann Yuan , Cheng Nan Han, Kou-Ning Chiang
		Department of Power Mechanical Engineering, National Tsing Hua University, HsinChu, Taiwan
		State of the Art in Prediction of Mechanical Behaviour of Microsystems
		M. Lishchynska, N. Cordero, O. Slattery
		NMRC, Lee Maltings, Prospect Row, Cork, Ireland
		Behavioral VHDL-AMS Modeling of Nuclear Magnetic Resonance Sensor
		S. Megherbi ¹ , JC. Ginefri ² , L. Darrasse ² , G. Raynaud ¹ , JF. Pône ¹
		¹⁾ Institut d'Electronique Fondamentale, France
		²⁾ Unité de Recherche en Résonance Magnétique Médicale, University of Paris-Sud, france
		3D-FEM Modelling of an Electro-Optical Micro-Shutter
		P. Roux ¹ , E. Woirgard ¹ , M. Pizz i^2
		¹⁾ IXL Laboratory, University of Bordeaux, Talence, France
		²⁾ Centro Ricerche Fiat (CRF), Orbassano, Italia
		Novel 2D Micronib Ionization Sources for Nano Electrospray-Mass Spectrometry (ESI-
		MS)
		S. Le Gac, ¹ S. Arscott ^{1,2} , C. Rolando ¹
		¹⁾ USTL, UPRESA CNRS 8009, Villeneuve d'Ascq Cedex, France
		²⁾ IEMN, UMR CNRS 8520, Villeneuve d'Ascq Cedex, France.

Session	n 12:	Poster session: Designing for Reliability
10.40	50	A Study of Cyclic Bending Reliability of Bare-die-type Chip-scale Packages
		Yi-Shao Lai1, Tong Hong Wang, Han-Hui Tsai, Jenq-Dah Wu
		Stress Characterization Laboratory, Advanced Semiconductor Engineering, Inc., Nantze, Kaohsiung,
		Taiwan
		Three-Dimensional Stress Analysis of Ink Marking Process
		Chang-Lin Yeh1, Yi-Hsien Lin, Yi-Shao Lai, Hsiao-Chuang Chang, Jenq-Dah Wu
		Advanced Semiconductor Engineering, Inc., Nantze, Kaohsiung, Taiwan
		Microprocessor Packaging Strategy: Reliability of various Flip Chip BGA Packages on
		different Printed Circuit Boards
		A. Guilhaume ¹ , C. Munier ¹ , C. Allégret ² , M. Michaud ²
		¹⁾ EADS CCR, Service DCR/EP/EO, SURESNES Cedex, France
		²⁾ MBDA, Vélizy Villacoublay, France
		Mechanism-Based Delamination Prediction During Reflow with Moisture
		Preconditioning
		X.J. Fan ⁴ , L.J. Ernst ¹ , G.Q.Zhang ² , W. van Driel ³
		¹⁾ Delft University of Technology, Delft, The Netherlands
		²⁾ Philips Cft, Eindhoven
		³⁾ ATO Innovation/Philips Semiconductors, Nijmegen, The Netherlands
		⁴⁾ Philips Research USA, New York, USA
		Microstructural Stability and Failure Modes in Eutectic Sn-Ag-Cu Solder
		M. A. Matin, W. P. Vellinga, and M. G. D. Geers
		Division of Materials Technology, Department of Mechanical Engineering, Eindhoven University of
		Technology, Eindhoven, The Netherlands
		Analysis of Thermal-Moisture Induced Failure of Pb-free Soldered IC Packages in SMT
		Reflow Soldering Process
		Ning Sun ¹ , Dachuan Lin ¹ , Daoguo Yang ^{1,2}
		¹⁾ Guilin University of Electronic Technology, Guilin, China
		²⁾ Delft University of Technology, The Netherlands

Session	n 13:	Poster session: Material Characterization and Modeling
10.40	50	Rupture Test on Polysilicon Films Through Electrostatic Actuation
		F. Cacchione ¹ , B. De Masi ² , A. Corigliano ¹ , M. Ferrera ²
		¹⁾ Department of Structural Engineering. Politecnico di Milano, Milano, Italy
		²⁾ MEMS Business Unit. STMicroelectronics, Cornaredo, (Milano), Italy
		Evaluation of the Primary and Secondary Creep of SnPb Solder Joint Using a Modified
		Grooved-lap Test Specimen.
		S. Déplanque ¹ , W. Nüchter ¹ , B. Wunderle ² , H. Walter ² , B. Michel ²
		¹⁾ Robert BOSCH GmbH, Stuttgart, Germany
		²⁾ IZM Fraunhofer Institut Zuverlässigkeit und Mikrointegration, Berlin, Germany
		Numerical Simulation and Experimental Verification of the Piezoresistivity Phenomenon
		for the Printed Thick-Film Piezoresitors
		A. Wymysłowski ¹ , M. Santo – Zarnik ^{2,3} , K. Friedel ¹ , D. Belavič ^{2,3}
		¹⁾ Wrocław University of Technology, Wrocław, Poland
		²⁾ Jožef Stefan Institute, Ljubljana, Slovenia ³⁾ HIPOT-R&D, Šentjernej, Slovenia
		Void Formation in a Copper-Via-Structure Depending on the Stress Free Temperature
		and Metallization Geometry
		K. Weide¹, D. Dalleau¹, Y. Danto², H. Fremont² ¹⁾ Laboratorium für Informationstechnologie, University of Hannover,, Germany
		²⁾ IXL, Universite Bordeaux I, Talence, France
		Mechanical Characterisation of SiLK by Nanoindentation and Substrate Curvature
		Techniques
		V. Gonda ¹ , K.M.B. Jansen ¹ , L.J. Ernst ¹ , Jaap den Toonder ¹ , G.Q. Zhang ³
		¹⁾ Delft University of Technology, Delft, The Netherlands
		²⁾ Philips Research Laboratories, Eindhoven, The Netherlands
		³⁾ Center for Industrial Technology/Philips, Eindhoven, The Netherlands
		Cantilever Microbeams: Modelling of the Dynamical Behaviour and Material
		Characterization
		R. Yahiaoui, A. Bosseboeuf
		Institut d'Electronique fondamentale, University of Paris-sud Orsay, Orsay, France
		A Novel Tool for Cure Dependent Viscoelastic Characterization of Packaging Polymers
		C. van 't Hof ⁴ , L.J. Ernst ¹ , K.M.B. Jansen ¹ , D.G. Yang ¹ , H.J.L. Bressers ² , G.Q. Zhang ³
		¹⁾ Delft University of Technology, Delft, The Netherlands
		²⁾ Philips Semiconductors, Nijmegen, The Netherlands
		³⁾ Center for Industrial Technology/Philips, Eindhoven, The Netherlands

			Parallel sessions
11.30-1	12.40	Session 14	Session 15
		Modeling of MEMS and Optical	Simulation-Based Thermal Design Strategies
		Devices	
Session	n 14:	Modeling of MEMS and Optical Device	es
11.30	30	Keynote: Hardware Description Langu	age Modeling of an Electrostatically Actuated bi-axial
		Micromirror	
		F. Parrain ¹ , S. Megherbi ¹ , G. Ray	ynaud ¹ , H. Mathias ¹ , J. Gilles ¹ , A. Bosseboeuf ¹ ,
		G. Schröpfer ² , P. Cusin ³ , N. Faur	re ³
		¹⁾ Institute d'Electronic Fondamen	ntale UMR8622 – Université Paris-Sud, Orsay Cedex, France
		²⁾ Coventor Sarl, Villebon, France ³⁾ Colibris SA, Neuchâtel, Switserle	
10.00	20		
12.00	20		SEL Array Multi-Physics Modelling for OECB Based
		Optical Backplanes D. $Comma1 B. Misselma k^{2,3} C. B$	Bailey ¹ , P.P. Conway ³ , K. Williams ³
			alley, F.F. Conway, K. Wullams and Process Analysis, University of Greenwich, London, UK
		²⁾ Celista, Stoke-on-Trent, UK	and Trocess Analysis, University of Greenwich, London, UK
			orough University, Loughborough, UK
12.20	20		tress in Glass Frit Bonded MEMS by Finite Element
		Analysis	
		M. Ebert, J. Bagdahn	
		Fraunhofer- Institute for Mechanic	cs of Materials Halle, Germany

Session	n 15:	Simulation-Based Thermal Design Strategies
11.30	30	Keynote: A Computer-Architecture Approach to Thermal Management in Computer Systems:
		Opportunities and Challenges
		K. Skadron, M.R. Stan, W. Huang, Zhijian Lu, K. Sankaranarayanan, J. Lach
		University of Virginia, USA
12.00	20	Tri-dimensional reduced-order Thermal Model of Stacked Electronic Structures
		V. Feuillet ¹ , V. Gatto ¹ , Y. Scudeller ² , Y. Jarny ¹
		1) Laboratoire de Thermocinétique
		2) Laboratoire de Génie des Matériaux
		Ecole polytechnique de l'université de Nantes, Nantes, France
12.20	20	Thermal Modeling for Power MOSFETs in DC-DC Applications
		Y. Bulut, K. Pandya
		Vishay Siliconix, USA

12.40 100 Lunch

14.20 Start Tuesday Afternoon Sessions

		Parallel sessions
14.20-16.10	Session 16	Session 17
	Solder Reliability Behavior	CFD and FE Modelling of Thermal Performance

Session 16:		Solder Reliability Behavior	
14.20	30	Keynote: Reliability of SnPb and Pb-Free Flip-Chips under Different Test Conditions	
		M. Spraul ¹ , W. Nüchter ¹ , A. Möller ¹ , B. Wunderle ² , B. Michel ²	
		¹⁾ Robert Bosch GmbH, Germany	
		²⁾ Fraunhofer-IZM, Berlin, Germany	
14.50	20	Microstructural and Mechanical Characterization of 95.5Sn-4Ag-0.5Cu Solder Balls by	
		Nano-Indentation	
		M. Erinç ¹ , P. Schreurs ¹ , G.Q. Zhang ¹ , W. D. van Driel ² , M. Geers ¹	
		¹⁾ Technical University of Eindhoven, Eindhoven, The Netherlands	
		²⁾ ATO Innovation/Philips Semiconductors, 6534 AE Nijmegen, The Netherlands	
15.10	20	Modeling Stress Strain Curves For Lead Free 95.5Sn-3.8Ag-0.7Cu Solder	
		J.H.L. Pang, B.S. Xiong and T.H. Low	
		Nanyang Technological University, School of Mechanical and Production Engineering, Singapore	
15.30	20	Effect of Different Temperature Cycle Profiles on the Crack Propagation and	
		Microstructural Evolution of Real Lead Free Joints of Different Electronic Components	
		C. Andersson ^{1,2} , D. Andersson ^{1,3} , P-E Tegehall ^{1,3} , Johan Liu ^{1,2,3}	
		¹⁾ Swedish Microsystem Integration Technology (SMIT) Center	
		²⁾ Division of Electronics Production, Chalmers University of Technology, Mölndal, Sweden	
		³⁾ IVF Industrial Research and Development Corporation, Sweden	
15.50	20	A Review of Creep Fatigue Failure Models in Solder Material - Simplified Use of a	
		Continuous Damage Mechanical Approach	
		G. Massiot, C. Munier	
		EADS Corporate Research Center, Suresnes cedex, France	

Sessior	n 17:	CFD and FE Modeling of Thermal Performance
14.20	30	Keynote: Thermal and Flow Analysis of SiC-Based Gas Sensors for Automotive Applications I. Below ¹ , P. Leisner ¹ , H. Wingbran ² , A.L. Spetz ² , H. Sundgren ² , B. Thuner ² , H. Svenningstorp ³ , P. Leisner ⁴ ¹⁾ Jönköping University, Sweden ²⁾ Linköping University, Sweden ³⁾ Volvo Technology Corporation, Sweden ⁴⁾ Acreo, Sweden
14.50	20	Low Reynolds Number Turbulence Models for Accurate Thermal Simulations of Electronic Components K Dhinsa, C Bailey, K Pericleous University of Greenwich, UK
15.10	20	Thermal Testing of a 3-Die Stacked Chip Scale Package Including Evaluation of Simplified and Complex Package Geometry Finite Element Models <i>B.A. Zahn</i> <i>ChipPAC, USA</i>
15.30	20	Thermal Analysis of QFN Packages Using Finite Element Method C.L. Chang, Y.Y. Hsieh National Yunlin University of Science and Technology, Taiwan
15.50	20	Experimental Study on Visualization of a Longitudinal Heat Sink with Top-mounted Fan by Particle Tracking <i>J.H. Jang</i> <i>Kuang-Wu Institute of Technology, Taiwan</i>

16.10 20 Break

	Special Exhibitor session
16.30	
10.00	End of and dow Technical Services

18.10	Cocktail reception







Wednesday May 12, 2004: Technical programme day 3

8.30		Start Wednesday Morning Sessions	
Session	ssion 18: Keynote session: Micro- to Macro-Scale Thermal Design Challenges in Microelectronics		
8.30	30	Keynote: Modeling Heat Transfer and Liquid Flow in Micro-Channels M.N. Sabry ¹ , B.O. Djebedjian ² , S.H. Saleh ² , M.M. Mahgoub ²	
		¹) Université Francaise d'Egypte, Egypt	
		²) Mansoura University, Egypt	
9.00	30	Keynote: Cooling Problems and Thermal Issues in High Power Electronics: a Multi-Faceted	
		Design Approach	
		M. Behnia ¹ , L. Maguire ² , G. Morrison ²	
		¹) The University of Sidney, Australia	
		²) University of New South Wales, Australia	
9.30	30	Keynote: Design Challenges for High-Performance Heat Sinks used in Microelectronic	
		Equipment: Evolution and Future Requirements	
		P. Rodgers ¹ , V. Eveloy ²	
		¹) CALCE Electronic Products and Systems Center, University of Maryland, USA	
		²) Electronics Thermal Management, Ltd., Ireland	

10.00 40 Break

	Parallel sessions	
10.40-12.30	Session 19 Session 20	
	Solder Fatigue	Characterization and Modeling of Polymer behavior

Session 19:		Solder Fatigue		
10.40	30	Keynote: A Mechanics-Based Strain Gage Methodology for Direct Solder Joint Reliability Assessment L.L. Mercado, S. Girouard, G. Hsieh Intel, Chandler, USA		
11.10	20	Microstructural Behaviour of Solder Alloys R.L.J.M. Ubachs, P.J.G. Schreurs, M.G.D. Geers Eindhoven University of Technology, Departement of Materials Technology, Eindhoven, The Netherlands.		
11.30	20	Flip Chip Solder Joint Fatigue Analysis Using 2D and 3D FE Models A. Yeo ¹ , C. Lee ¹ , J. H.L. Pang ² ¹⁾ Infineon Technologies Asia Pacific Pte Ltd, Assembly & Interconnect Technology, Singapore ²⁾ *School of Mechanical and Production Engineering, Nanyang Technological University, Singapore		
11.50	20	Thermal Fatigue Modelling for SnAgCu and SnPb Solder Joints <i>R. Dudek, H. Walter, R. Doering, B. Michel</i> <i>Fraunhofer IZM, Berlin, Germany</i>		
12.10	20	Thermal Cycling Reliability of SnAgCu and SnPb Solder Joints: A Comparison for Several IC-Packages B. Vandevelde, M. Gonzalez, P. Limaye, P. Ratchev, E. Beyne IMEC, Leuven, Belgium		

Session	n 20:	Characterization and Modeling of Polymer behavior
10.40	30	Keynote: Molecular Modeling Studies of IC Barrier Concerns.
		N. Iwamoto,
		Honeywell Specialty Materials, Morristown, USA
11.10	20	Molecular Simulation of Cu-SAM Adhesion Force
		H. Fan, C.K. Wong, M.M.F. Yuen
		Department of Mechanical Engineering, Hong Kong University of Science and Technology, Kowloon,
		Hong Kong
11.30	20	Cure, Temperature and Time dependent Constitutive Modeling of Moulding
		Compounds
		K.M.B. Jansen ¹ , L. Wang ¹ , D.G. Yang ¹ , C. van 't Hof ¹ , L.J. Ernst ¹ , H.J.L. Bressers ² , G.Q. Zhang ³
		¹⁾ Delft University of Technology, Delft, The Netherlands
		²⁾ Philips Semiconductors, Nijmegen, The Netherlands
		³⁾ Philips CFT, Eindhoven, The Netherlands
11.50	20	Simulation of No-Flow Underfill Process for Flip-Chip Assembly
		A. Kolbeck ¹ , T. Hauck ¹ , J. Jendrny ² , O. Hahn ² , S. Lang ³
		¹⁾ Motorola GmbH, Deutschland
		²⁾ LWF, Universität Paderborn, Deutschland
		³⁾ CADFEM Gmbh, Grafing, Germany
12.10	20	Mechanical Properties of Molding Compounds (MCs) under Different Moisture
		Conditions and in a Wide Temperature Range
		W.H. Zhu, S. L. Gan, C.L. Toh
		Assembly and Interconnect Technologies, Infineon Technologies Asia Pacific Pte Ltd, Singapore

12.30 90 Lunch

14.00 Start Wednesday Afternoon Sessions

Sessior	ı 21:	Keynote session: New Developments in Microelectronics Reliability
14.00	30	Keynote: Challenges of Thermomechanical Design and Modeling of Ultra Fine-Pitch Wafer Level
		Packages
		A. A. O. Tay
		Department of Mechanical Engineering, Nano/Microsystems Integration Laboratory,
		National University of Singapore, Singapore
14.30	30	Keynote: Topography and Deformation Measurement under Thermomechanical Stress
		R. Fayolle, J. Lecomte
		Insidix, Seyssins, France
15.00	30	Keynote: Reliability of Interfaces for Lead-Free Solder Bumps
		R.L.H. Shih ¹ , D.Y.K. Lau ² , R.W.M. Kwok ^{2*} , M. Li ³ , M.K.W. Sun ⁴
		¹⁾ Department of Chemistry, The Chinese University of Hong Kong, Shatin, N.T., Hong Kong
		²⁾ Rohm and Haas Electronic Materials Asia Limited, 15 On Lok Mun Street, Fanling, N.T., Hong Kong
		³⁾ Department of Electronic Engineering, The Chinese University of Hong Kong, Shatin, N.T., Hong
		Kong
		⁴⁾ Department of Physics, The Chinese University of Hong Kong, Shatin, N.T., Hong Kong
15.30	30	Keynote: From Chemical Building Blocks of Polymers to Microelectronics Reliability
		H.J.L. Bressers ² , W.D. van Driel ³ , K.M.B. Jansen ¹ , L.J. Ernst ¹ and G.Q. Zhang ³
		¹⁾ Delft University of Technology, Delft, The Netherlands
		²⁾ Philips Semiconductors, Nijmegen, The Netherlands
		³⁾ Philips CFT, Eindhoven, The Netherlands

16.00 End of Conference

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Location of courses + hotel info

IMEC Kapeldreef 75, 3001 Leuven, Belgium

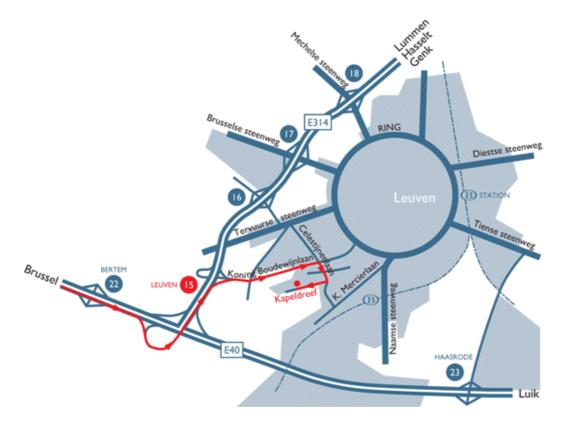
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How to reach IMEC:

By car: IMEC is located in Heverlee, Leuven, approximately 25 km from both Brussels and International Airport "Zaventem". It takes half an hour drive by car to reach IMEC from Brussels, capital of Belgium. Leuven lies at the intersection of two highways, the E40 highway London (GB) - Brussels - Liège - Köln (Germany) and the E314 highway Leuven-Hasselt-Aachen (Germany). For a visual representation, see our map. Taxi fare from Brussels city centre to IMEC is approximately 50 Euro.

By train: Leuven is situated along the international rail line serving London (GB) - Brussels - Liège - Köln (Germany). If you are travelling from another direction then the ones mentioned above, a changeover at Brussels' North, Central or South Station is needed to reach Leuven. If you are coming from Brussels airport, take the underground station located in the airport building to reach Brussels Station North (Noord). From this station you can take the train to Leuven. For more information about the Belgian Railroad company "NMBS" and its trains go to <u>www.nmbs.be</u>. Taxi fare from Leuven station to IMEC is approximately 10 Euro.

By Bus: From Leuven station or downtown Leuven city, bus 2 - CAMPUS will bring you to the Kapeldreef in Heverlee (terminus). The bus stop is situated just opposite of the IMEC building. For more information about the Flemish bus company "De Lijn" go to <u>www.delijn.be</u>



Hotels in Leuven (to stay from May 8th to May 9th): <u>http://www.book-a-hotel-in-leuven.com/</u> (closest hotel to IMEC: The Lodge in Heverlee: <u>http://www.lodge-hotels.be/</u>)

Conference location



NOVOTEL Tour Noire Rue de la Vierge Noire 32, B-1000 Brussels, Belgium Phone +32(0) 2 505 50 50, Fax +32(0) 2 505 50 00 Internet: <u>www.novotel.com</u>; Email: <u>H2122@accor-hotels.com</u>



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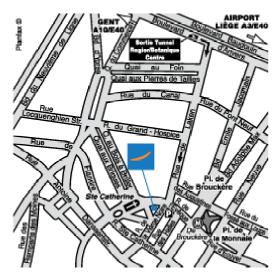


Conference hotel:

We advise that you book your hotel by **March 2004** at the latest, as Brussels is a tourist city, having pleasant weather. Since the conference will be held at the Novotel Brussels Centre Tour Noire, a special room rate, if booked early enough, will be offered to conference attendees:

- single room: 145 Euro/night per room, breakfast included;
- double room: 160 Euro/night per room, breakfast included.

Please refer to the conference when reserving a room-("Eurosime meeting 10-12th May 2004").



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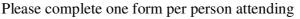
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Date of arrival	D	ate of departure		
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Registration form



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Sunday May 9 : 9.00 to 12.30, in Leuven (IMEC)	Sunday May 9: 13.30 to 17.00, in Leuven (IMEC)
C2: Application of static and dynamic compact thermal models	C3: Heat sink design and analysis for microelectronic equipment
C4: Advanced optimization methods for design and qualification	C5: Lead-free solder joints: Reliability trends and material Properties
C6: Fundamentals of board-level assembly and solder joint reliability	C7: µ-vias and high density interconnects for advanced packaging
C8: Wafer level packaging technologies	

The conference on May 10-12, in Brussels	Vegetarian lunches Vegetarian dinner (Monday May 10)
The dinner on Monday May10 (free for participants)	Other food requirements:

Participation to the conference includes access to exhibition, lunches, social event, cocktail party, proceedings of the conference (bound + CD)

Price calculation:

Item	Price early registration (before April 24 th)	IEEE member Number:	Supplement for late registration (after April 24 th)	Your price
Conference	550€	495 €	+ 100 €	
One course $(C2 - C8)$	250€	225€	+ 100 €	
Two courses (or C1)	400 €	360€	+ 100 €	
Programme for accompanying person (Brussels, 1 day visit): 100 €				

TOTAL =

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